WEST Search History

DATE: Friday, May 23, 2003

Set Name	Query	Hit Count	Set Name
side by side			result set
	DB=USPT,PGPB,JPAB,EPAB,DWPI,TDBD; PLUR=YES; OP=ADJ		
L6	L1 and (control$5 same (UV or IR or wavelength or absorbance or refraction))	57	L6
L5	L4 and l3	0	L5
L4	((134/18 |134/56R |134/902)!.CCLS. |(438/906)!.CCLS.)	3193	L4
	DB=USPT,JPAB,EPAB,DWPI; PLUR=YES; OP=ADJ		
L3	L1 same (UV or IR or wavelength or absorbance or refraction)	43	L3
L2	L1 same (control$5 with (UV or IR or wavelength or absorbance or refraction))	0	L2
L1	(clean$3 or etch$3 or remov$3 or rins$3 or treat$3) same (substrate or semiconductor or wafer) same ((ammonium fluoride)or 'NH.sub.4 F')	1850	L1

END OF SEARCH HISTORY